Abstracts

Millimeter Resonance Isolator Utilizing Multilayer Ni and NiZn Ferrite Films (Correspondence)

W.L. Wade, Jr., R. Stern and T. Collins. "Millimeter Resonance Isolator Utilizing Multilayer Ni and NiZn Ferrite Films (Correspondence)." 1965 Transactions on Microwave Theory and Techniques 13.1 (Jan. 1965 [T-MTT]): 127-128.

This communication describes a significant improvement in the performance of a resonance isolator in the 35-Gc/s frequency region utilizing chemically deposited ferrite films. The performance of a millimeter resonance isolator utilizing single-layer ferrite films was reported earlier. In the device described here an improvement in the isolator performance was achieved by utilizing combinations of Ni and NiZn chemical formulations to form new multilayer ferrite films. A description of the device configuration, isolation characteristics, and modification of previous chemically deposited ferrite film techniques is included.

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